Evaluation of analytical instrumentation

Part XXIV. Instrumentation for quadrupole inductively coupled plasma mass spectrometry

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A C I C -C .

Introduction

-C A C, G f (C), C. B , J. H , K. E. J. , G. L , J. J. J. E. J. K. E. J. I C -C .A .I .I .I C .I I -C -

H ,

C 1.
C 2.
C 3. -C

Notes on the use of this document

F
I G 9000

Other reports

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An overview of inductively coupled plasma mass spectrometry (ICP-MS)

Introduction

I (IC -), IC
A
A (IC) . A
IC -

Key features

IC -

(*Cont'd.*)

AA	$L^{\square 1}$ μ $L^{\square 1}$	. L	
F	μ $L^{\square 1}$	. L	

* : $L^{\square 1}$ ¼ 1 10^{12}, $L^{\square 1}$ ¼ 1 10^{9}, μ $L^{\square 1}$ ¼ 1 10^{6}.

F	I
L	
(a) Previous instruments	
( ) I	C I IC -
( )	C I
( ) & ( )	F H I . I
( ) C f	C f I f
(b) Servicing	( ) :
( )	A D I E
( ) A	I
( ) E	I A
(c) Technical support	( ) : I ( )/I
( ) A	
( )	
( )	I
( )	I A
( ) &	

(*Cont'd.*)

F	I
I	
1. High frequency (HF) generators	27 H A
(*a*)	( ). IC - HF
(*b*)	A HF I I

(*Cont'd.*)

F		I
( ) C	f	

(C ...d.)

F		I	
C			

(

(*Cont'd.*)

F	I	A
(*c*)		
5. Interface		IC
(*a*) C	I	I
(*b*) E	I	E
(*c*) C	I	
(*d*) I	I	
(*e*) C		C
6. Vacuum system	I	
7. Ion detector		
(*a*)		C

(*Contd.*)

(*Continued*)

F	I

8. Instrument control and monitoring

(*a*) I

(*Cont'd.*)

(*d*)		

(*Cont'd.*)